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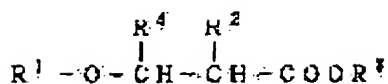
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(54) RADIATION SENSITIVE COATING COMPOSITION

(57)Abstract:

PURPOSE: To provide a radiation sensitive coating compsn. ensuring satisfactory coatability and less liable to foam.

CONSTITUTION: In a radiation sensitive coating compsn. contg. a base resin, a radiation sensitive compd. and a solvent, a solvent contg. a compd. represented by the formula is used as the solvent and a nonionic fluorine-contg. surfactant is also contained. In the formula I, each of R1-R3 is optionally halogen-substd. methyl or ethyl and R4 is H, optionally halogen-substd. methyl or ethyl.



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